

Client Reference: P-1586.010-US

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

JOERI LOF, et al.

Application No.: 10/705,816

Filed: November 12, 2003



Group Art Unit: 2878

Examiner: Lu, Tony W.

Confirmation No.: 5408

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
 P. O. Box 1450  
 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. One copy of each non-U.S. reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicant respectfully requests the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicant with the next Office communication to indicate that the references have been considered, per MPEP § 609.

This Information Disclosure Statement is being filed after the mailing of the first official action on the merits but before the mailing date of a Final Rejection or Notice of Allowance. Please charge Deposit Account 033975 in the amount of \$180.00 in payment of the fee under 37 CFR 1.17(p) pursuant to 37 CFR 1.97(c)(2). Please credit or debit Deposit Account 033975 as needed to ensure consideration of the disclosed information.

Respectfully Submitted,

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04/11/2006 JAH/01 00000008 033975 10705816

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Date: April 10, 2006

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JRM PT<sup>O</sup>-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office



Atty. Dkt. No.	M#	Client Ref.
	306525	P-1586.010-US
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Applicant: LOF et al.		
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Examiner: Unknown		
Group Art Unit: 2882-2878		

INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT

Date: January 7, 2005

Page: 1 of 2

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (If appropriate)
TL AR	4,390,273	06/1983	LOEBACH et al.	355	125	
TL BR	6,603,130	08/2003	BISSCHOPS et al.	250	492.1	
TL CR	6,633,365	10/2003	SUENAGA	355	53	
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TL ER	2003/0123840	07/2003	ALMOGY	355	69	
TL FR	2003/0174408	09/2003	ROSTALSKI et al.	359	842	
TL GR	2004/0075895-A1	04/2004	LIN	359	380	
TL HR	2004/0109237 A1	06/2004	EPPEL et al.			
TL IR	6,236,634 B1	05/2001	LEE et al.	369	112	
TL JR	2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	
TL KR	2004/0119954	06/2004	KAWASHIMA et al.	355	30	
TL LR	2004/0125351	07/2004	KRAUTSCHIK et al.	355	53	

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					Enclosed	No	Enclosed	No
TL MR	JP 04-305915	10/1992	JAPAN	OZEKI et al.		X		
TL NR	JP 04-305917	10/1992	JAPAN	OZEKI et al.		X		
TL OR	JP 06-124873	05/1994	JAPAN	TAKAHASHI		X		X
TL PR	JP 07-220990	08/1995	JAPAN	FUKUDA et al.				
TL QR	JP 10-228661	08/1998	JAPAN	KUROKAWA		X		
TL RR	JP 10-255319	09/1998	JAPAN	SUENAGA et al.		X		
TL SR	JP 10-303114	11/1998	JAPAN	SUWA		X		X
TL TR	JP 10-340846	12/1998	JAPAN	KUDO		X		X
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OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

TL WR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002							
TL XR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997							
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TL ZR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22							
TL AAR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004							
BBR								

Examiner *[Signature]* Date Considered: *12/2005*  
 \*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)  
 To: U.S. Department of Commerce  
 (PW FORM PAT-1449)  
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**INFORMATION DISCLOSURE STATEMENT**  
**BY APPLICANT**

Date: April 10, 2006

Page **1** of **1**

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081468	0306525	P-1586.010-US
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Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
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	BR	2005/0219489	10/2006	NEI ET AL.	355	53	
	CR	2005/0200815	09/2005	AKAMATSU	353	53	
	DR						
	ER						

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		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
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	GR	WO 2004/102646	11/2004	PCT	ISHII		X		
	HR	WO 2005/031799	04/2005	PCT	NISHINAGA ET AL.		X		
	IR	WO 2005/036624	04/2005	PCT	YASUDA ET AL.		X		
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	KR								
	LR								

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

MR	European Search Report for EP Application No. 03257072.3, dated June 23, 2005.		
NR			
OR			

Examiner

Date Considered:

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